

**AMENDMENTS TO THE CLAIMS**

**This listing of claims will replace all prior versions and listings of claims in the application:**

**LISTING OF CLAIMS:**

1-21. (canceled).

22. (previously presented): An n-channel or ambipolar field-effect transistor including an organic semiconductive layer having an electron affinity  $EA_{\text{semicond}}$ ; and an organic gate dielectric layer forming an interface with the semiconductive layer; characterised in that the bulk concentration of trapping groups in the gate dielectric layer is less than  $10^{18}\text{cm}^{-3}$ , where a trapping group is a group having (i) an electron affinity  $EA_x$  greater than or equal to  $EA_{\text{semicond}}$  and/or (ii) a reactive electron affinity  $EA_{\text{rxn}}$  greater than or equal to  $(EA_{\text{semicond}} - 2\text{eV})$ .

23. (previously presented): A transistor according to claim 22, wherein the transistor is an ambipolar field-effect transistor.

24. (previously presented): A transistor according to claim 22 wherein  $EA_{\text{semicond}}$  is greater than or equal to 2eV.

25. (previously presented): A transistor according to claim 24 wherein  $EA_{\text{semicond}}$  is in the range of from 2eV to 4eV.

26. (previously presented): A transistor according to claim 22 wherein the gate dielectric layer comprises an organic insulating material and the organic insulating material does not contain a repeat unit or residue unit comprising a trapping group.

27. (previously presented): A transistor according to claim 22, wherein the insulating material does not contain a repeat unit or residue unit comprising a group having (i) an electron affinity  $EA_x$  greater than or equal to 3eV and/or (ii) a reactive electron affinity  $EA_{\text{rxn}}$  greater than or equal to 0.5eV.

28. (previously presented): A transistor according to claim 27 wherein the insulating material does not contain a repeat unit or residue unit comprising a quinone, aromatic -OH, aliphatic -COOH, aromatic -SH, or aromatic -COOH group.

29. (previously presented): A transistor according to claim 22, wherein the insulating material contains one or more groups selected from alkene, alkylene, cycloalkene, cycloalkylene, siloxane, ether oxygen, alkyl, cycloalkyl, phenyl, and phenylene groups.

30. (previously presented): A transistor according to claim 22 wherein the insulating material comprises an insulating polymer.

31. (previously presented): A transistor according to claim 30, wherein the insulating polymer is selected from the group consisting of substituted and unsubstituted poly(siloxanes) and copolymers thereof; substituted and unsubstituted poly(alkenes) and copolymers thereof; substituted and unsubstituted poly(styrenes) and copolymers thereof; and substituted and unsubstituted poly(oxyalkylenes) and copolymers thereof.

32. (previously presented): A transistor according to claim 31, wherein the backbone of the insulating polymer comprises a repeat unit comprising  $-\text{Si}(\text{R})_2-\text{O}-\text{Si}(\text{R})_2-$  where each R independently is methyl or substituted or unsubstituted phenyl.

33. (previously presented): A transistor according to claim 30, wherein the insulating polymer is crosslinked.

34. (previously presented): A transistor according to claim 22 wherein the organic semiconductive layer comprises a semiconductive polymer.

35. (previously presented): A transistor according to claim 22 wherein the organic semiconductive layer comprises a semiconductive oligomer.

36. (previously presented): A transistor according to claim 22 wherein the organic semiconductive layer comprises a semiconductive small molecule.

37. (previously presented): A method for making a transistor as defined in claim 22.

38. (previously presented): Use of a transistor according to claim 22 for n-channel conduction in an n-channel or ambipolar field effect transistor.

39. (previously presented): Use of an organic gate insulating material that does not contain any chemical groups having (i)  $\text{EA}_x$  greater than or equal to 3eV and/or (ii)  $\text{EA}_{\text{rxn}}$  greater than or equal to 0.5eV, for n-channel conduction.

40. (previously presented): Use according to claim 39, wherein the insulating material does not contain any chemical groups having (i)  $EA_X$  greater than or equal to 2eV and/or ( $EA_{rxn}$ ) greater than or equal to 0eV.

41. (previously presented): A circuit, complementary circuit, or logic circuit including a transistor as defined in claim 22.

42. (previously presented): A method for making a circuit, complementary circuit, or logic circuit as defined in claim 41.